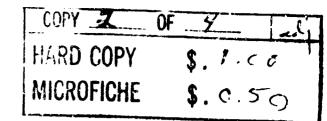
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TRANSLATION

THE CELLULAR STRUCTURE OF THICK-LAYERED ANODIC COIDE FILMS

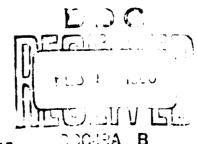
By

N. D. Tomashov and F. F. Zalivalov

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THE CELLULAR STRUCTURE OF THICK-LAYERED ANODIC OXIDE FILMS

BY: N. D. Tomashov and F. P. Zalivalov

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THE CELLULAR STEUCTURE OF THICK-LAYERED ANODIC OXIDE FILMS By N. D. Tomashov and F. P. Zalivalov

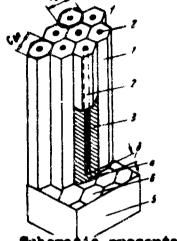
Thick-layered exide films (of a thickness of 25 to 200 microns) anodically formed on the surface of aluminum and its alloys have great practical significance due to such valuable properties as high resistance to wear by attrition, high heat and electrical insulation qualities, condiderable toughness in meshing with other metals, and high resistance to corrosion [1-3]. The properties of anodic exide films are determined by their structure, which in turn depends on the conditions of the electrolysic.

A considerable amount of work has been devoted to the investigation of the structure of anodic films obtained on pure aluminum by foreign and domestic authors [4-8], according to which the structure of these films represents a dense packing of exide units of hexagonal form set perpendicularly to the surface of the metal and solidly welded to each other by their lateral faces (Fig. 1). Buch unit (or cell) consists of a centrally located pure, the walls of the exide cell, and a thin layer of exide of the barrier type (barrier film) as its basis. The diameter of the pore is determined mainly by the character of the electrolyte and does not depend on other conditions of the anode process.

The study of the structure of the anodic oxide films, along with a great deal of theoretical interest, has direct practical significance, inamuch as it enables one to mark out ways for the creation of new coatings with properties given beforehand and also to proceed to the explanation of the structure and properties of anodic films obtained on aluminum allows. The purpose of this

present work is centered in the determination of the quantitative interconnection between the thickness of the barrier layer of the film and the dimensions of the oxide cells.

For objects of research there were chosen specimens of aluminum of the brand AVOOO (99.99% Al) which were then apodically oxidized (anodized) in 4-m " with ourrent densities of 2.5; 5, and 10 smp/dm and the shaping voltages corresponding to them (B) 22, 25, and 27 v. The temperature of the electrolyte during the anodising was maintained at about -- 2 . For comparison we research-



Pig. 1. Schematió presentation of the structure of the cells obtained in anodic oxidation of aluminum sulfurio soid, 1-oxide cell,2-pore. 3-wall of oxide cell.4-bamoval of anode film: C bed in hemagon. C is the same but for circumscribed

ed the structure of the anodic cell obtained in the ordinary procedure of the anodic process: density of the ourrent 1 amp/dm2 (shaping voltage 10v), temperature of electrolyte 20 . The procedure and conditions of the snodising are described more in detail in other reports [9, 10]. The dimensions of the oxide cells are determined from photographs obtained with the electron microscope FM-) with the sid of collodion and carbon mplices [8]. The thickness of the barrier layer of the anodic film was determined by the electrochemical method [11], based on the measurement of rrier layer, 5-sluminum, 6- the dependence, voltage-amperage in alkalised 3impressions of oxide cells on percent solution of warteric acid (pH = 5.5) in surface of aluminum after re- which the rate of the growth of the barrier is equal to 14 A/v. In accordance with these data the dimension of oxide cell equal thickness of the barrier layer (A) is equal to the to diameter to circle insori- fourteenfold maximum terminal voltage of the circuit is volts at which the current does not rise sharply. The latter is observed at the rise above the

cont. Fig. 1.
circle, 8--thickness of
barrier layer

voltage at which there was formed the given barrier layer.

In the article two questions are considered.

1. Resping in mind that the oxide film is formed in the barrier layer it is natural to assume a definite dependence between the thickness of the barrier layer and the size of the exide coll (See Fig. 1). The first attempt to find such a dependence was made on the basis of theoretical premises in the report [4] in which the rolationship between the size of the cell CBT, equal to the disaster of the circle inscribed in the hexagonal cell and the thickness of the barrier layers is expressed by the formula $c_{Bi} = \sqrt{26}$. In the following work [5] the connection between the size of the cell and the thickness of the barrier layer, which was obtained on the basis of experimental data, is determined by the equation C $BR = 1.67 \delta + p$, where p is the size (diameter) of the pore. In the work [7] it is pointed out that in accordance with calculations the distance between the pores cannot expeed twice the thickness of the barrier layer and ordinarily is equal to its thickness, i. e., one can write that $\operatorname{CB}_{\Pi} \approx 4$. By rewriting the above-presented equations $C_{BN} = \sqrt{2\delta}$, $C_{BN} = 1.67 \delta + p$ and $C_{BN} \approx 6$ in the form of a ratio of the thickness of the wall of the oxide cell (CBn-p) to the thickness of the barrier layer (8) we shall have correspondingly

$$\frac{C_{nn}-p}{28} < 0.7$$
, $\frac{C_{nn}-p}{28} = 0.835$ и $\frac{C_{nn}-p}{28} < 0.5$,

i. e., the ratio $\frac{C_{B\eta-\eta}}{2}$ which characterises the connection of the thickness of the wall of the oxide sell with the thickness of the barrier layer in all cases less than unity.

In Table 1 there are shown the figures for the dimensions of the described cells of anodic films and the thickness of the parrier layer corresponding to them, which were obtained experimentally for four procedures of anodic oxidation of aluminum. Since the cell has a six-sided form in the table there are given two

dimensions of the oxide cells one equal to the diameter of a circle described in the hexagon $(C_{\rm BH})$ and another equal to the diameter of a circumscribed circle $(C_{\rm O,1})$.

The ratio of the thickness of the well of the oxide cell to the thickness of the barrier layer, i. e., the anguitude $\frac{C_{1}}{2C_{0}}$ as is seen from Table 1, lies within the limits of 0.802 to 0.811. The ratio $\frac{C_{0}}{2C_{0}}$ computed from the cell equal to the diameter of circle circumscribing the heragon is equal to 0.958—9.994, i. e., to the greatest degree approaches unity. In fact the most probable ratio, so it seems, will be the equality $\frac{C_{0}}{2C_{0}} = 1$, where C_{0} is the maximum possible dimention of the cell (according to the circumscribed circle). Then the greatest alignitude of the size of the cell in accordance with inscribed circle (C_{0}^{i}) will be equal to C_{0}^{i} where k is the coefficient which determines for the correct heragon the ratio of the diameter of the circumscribed circle to the diameter of the inscribed circle (k = 1.154). In this way one may conclude that the basic relationship which determines the structural parameters of the thick-layer ancdic film is the equation $\frac{C_{0}}{R} = 1$. The figures of the dimensions of the oxide cell are determined in the following form: $C_{0}^{i} = 26 + p$ and $C_{0}^{i} = \frac{C_{0}^{i}}{R}$ All other relationships prove is be more or less precise approximations to these equations.

As an example which confirms the close connection of the thickness of the barrier layer with the size of the oxide cell one may use the temperatures given in accordance with the effect on them. As is seen from Fig. 2 and Fig. 3, with the rise in the temperature of the electrolyte, there is a drop in the thickness of the barrier layer and the size of the oxide cell. Since the two experiments were set up in somewhat 41 man to additions they do not allow a numerical comparison of these values. However, the conformity to law in the two cases is identical.

2. In the research of the cellular structure of the thick-layered anodic films the most characteristic form of the mutual orientation is the strict

Structural characteristics of anodic oxide films obtained on aluminum with ordinary and thick-layered anodising in 4-n H₂SO₄

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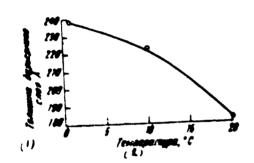
Density Shaping Com- Com- Thick- Inverse of the Randio Sarited puted puted ness Com- Com- Thick- Com- Com- Sarited scribed layer barrier 76 76 76 76 76 76 76 76 76 76 76 76 76

constant and equal to 20 A

^{**}a -- overall thickness of anoth film

crierliness (regularity) in the arrangement of the oxide cells. This can be seen from Fig. 4, a and b, where there are presented the electron-microscope pictures obtained by us of the cellular structure in two mutually perpendicular planes. As is seen from Fig. 4, a, each cell, judging by its impression on the photograph, borders on six adjoining cells, forming a solid packing of hexagons, reminding one of a beehive. As is known the most solid packing of spheres is such ar arrangement of them that each sphere has six neighbors in contact with it. There is no other way of arranging a solid layer of spheres, and the bases of oxide cells represent spheres, close in their geometry to hemispheres. Therefore the form of the oxide cells corresponds to the form of he ranedrons.

In accordance with our concept the orderly cellular structure is formed



1-n R,30 1

Fig. 2. Effect of temperature Fig. 3. Effect of temperature on size of electrolyte on the thick- of oxide cells of anodic oxide film ness of the barrier layer ob- obtailed under following conditions: tained on pure aluminum in 99.49-percent Al, 4-n 1,804. Da = 2.5 amp/dm2, 7 = 60 min

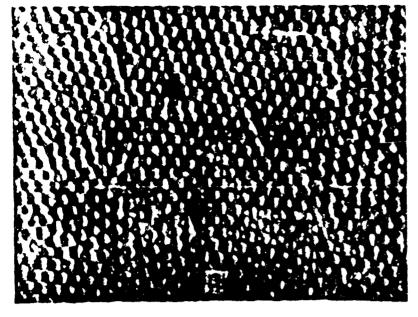
Legend: (1) thickness of barrier layer, (2) temperature, (3) give of exide cells, (4) temperature.

lowing way. In the beginning after the formation of the thin nonporque oride film of the barrier type on the sur-

in the fol-

face of the metal in the process of its anodising there are formed separate cells corresponding to those places in the film where the pores are formed. The presence of such places is determined by some kind of defects in the barrier film which more easily are subjected to the caustic action of the

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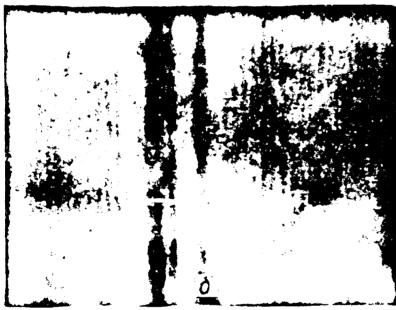


Fig. 4. Electron-microscope photographs obtained of the surface of the aluminum after removing the anode film (a) and from the surface of the longitudinal shear of the film (b). The film was obtained in 4-n. $\rm H_2SO_4$ at D_a + 5 amp/dm². Collodion-carbon impression: a - x22,000; b - x16,000.

electrol; te.

As the chaping voltage between the existing cells increases new cells are formed gradually filling the whole surface of the metal. Apparently, even an earlier formed hemisphere of a cell cannot grow unlimitedly, since its dimensions will be determined by the applied voltage and the conductivity of the film. However, without doubt in the init'al moment of the formation of the film the dimensions of the cells will be naturally somewhat different from each other, since later the formation of cells will give less time for their growth, and the centers of the dells will be arranged chaotically without any definite orientation. Such

a situation refers to the initial period of the formation of the porous part of the film.

After the separate cells lock together and cover the whole surface of the metal the cells can then only grow in depth. Under these conditions, apparently, each crids cell which has a lesser hemisphere (having delayed from the beginning of the growth) will have more possibility for growth since these cells are distinguished by the lesser thickness of the barrier layer.

In this way in the beginning of the process of the formation of the porous part of the film there is observed a certain disorder, irregularity in the structure of the exide cells.

One may assume two variants of the transition to the strictly orderly cellular structure. The first consists in the "squeezing" of some cells by others, i. e., separate cells will in the process of their growth in depth gradually crowd their neighbors, lining up as to dimensions and and regrouping so as to create as much as possible a more compact packing. But in this case the number of orlis coming into existence at the very beginning should be preserved throughout the whole anodic process. Since the number of first cells can in general be indefinite (i. e., their number to a greater or lesser degree differs from the number of cells corresponding to an orderly structure), therefore the average dimensions of the cells in each separate case should vary, which, as is known, is not so in practice.

The second, as it seems to us, more real variant consists in the reorganisation of the cells themselves in the process of their growth. In this case the rearranging of the cells results in this that out c a greater number of cells a smaller number is formed—too often the arranged cells will blend. Such a reorganisation is schematically presented in Fig. 5. As a result the cells are aligned in accordance with their dimensions. But in this case the cells will tend to align themselves not in a general way but around a definite maximum dimension determined by the equation $\frac{\text{Con-p}}{2\delta} = 1$. Only efter this each cell gets equal possibility for its growth. And as about

as the dimensions of the cells become identical the scheme of their arrangement takes on a strictly orderly appearance. This will correspond to the stabilisation of the structure of the anodic film.

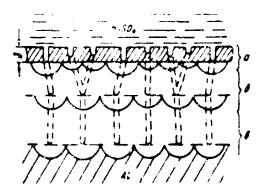


Fig. 5. Scheme of the arrangement of the orderly cellular structure on the surface of aluminum with aniform structure of the metal: a—initial moment (disorderly structure); b—rearrangement of the structure, o—orderly (regular) structure.

Eation was shown in the following experiment. At the time of the anodising the density of the current changed (from 2.5 to 10 amp/dm² and vice versa). After this the electron-microscopy investigated the cellular structure on the boundary separating the metal and the cells (after removal of the film). As is seen from Table 2 with the change in the density of the current there was a change also in the dimensions of the oxide cells (and consequently of their number), i. e.,

Table 2

Dimensions of Oxide Cells with Change of Density of Current in the Process

Oxidation of Aluminum (4-n. H₂30₄, t = --2*)

dammite	time of anodic	sise of	Change in a	ise of cell, A	
of ourrent amp/dm ²	oxida- tion, min	oella Å	theoretical	observed	
2.5 10	10 10	48 0 550		_	
2.5 -1 0 10 -2. 5	10510 10410	560 490	+70 -7(+80 -60	

there occurs a reorganisation in the structure of the film itself (the plus sign indicates increase in the size of cells; the minus sign, decrease). In this way the reorganisation of the structure of the oxide cells in the process of anodic exidation is quite possible.

Conolusions

1. It was been shown that the basic ratio which determines such structural parameters of a thick-layer anodic film as the size of the oxide cell (C_{OR}^4) and the thickness of the barrier layer is the equation

25 25

where p is the diameter of the pore.

2. There has been presented the mechanism for the formation of the order1/ pellular structure according to which with the shaping of the oxide cells
there occurs not only a qualitative (change of dimensions) but also a quantitative reorganisation of the cellular structure.

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